CLAIMS

1. A mold for imprint, comprising a leveling agent layer with a desired uneven pattern formed on an outermost surface, by embedding and leveling unevenness on a main surface of a base body by coating this portion with a leveling agent.

2. The mold for imprint according to claim 1, wherein the base body is a cylindrical substrate.

3. The mold for imprint according to claim 1 or 2, wherein the leveling agent layer is made of polysilazane.

4. A method for manufacturing a mold for imprint, comprising:

forming a leveling agent layer on a base body for leveling the base body by embedding an unevenness on a main surface of the base body by coating this portion with a leveling agent; and

forming a desired uneven pattern on the main surface of the leveling agent layer itself by etching.

5. The method for manufacturing a mold for imprint according to claim 4, wherein the base body is a cylindrical substrate.